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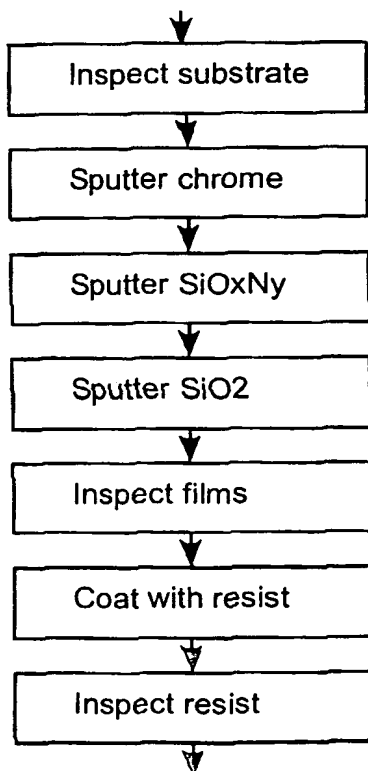
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(54) Title: A MASK BLANK AND A METHOD FOR PRODUCING THE SAME

(57) Abstract: An aspect of the present invention includes a method for manufacturing a mask blank. A substrate is provided. A masking layer is formed on said substrate. At least one layer of material is formed on said substrate such that a reflectivity of a writing wavelength to a film sensitive to the writing wavelength is below 4 %. Other aspects of the present invention are reflected in the detailed description, figures and claims.



WO 03/085362 A1